



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of:

WANG YUEH, ET AL.

Application No.: 10/687,288

Filed: October 15, 2003

For: **METHODS AND COMPOSITIONS FOR
REDUCING LINE WIDE ROUGHNESS**

Art Group: 1756

Examiner: Daborah Chacko Davis

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Commissioner for Patents
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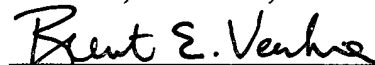
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Respectfully submitted,

BLAKELY, SOKOLOFF, TAYLOR & ZAFMAN LLP

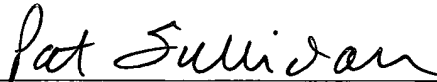
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Brent E. Vecchia, Reg. No. 48,011

12400 Wilshire Boulevard, 7th Floor
Los Angeles, CA 90025
Telephone: (408) 720-8300

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STATEMENT BY APPLICANT**

Sheet

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of

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Complete if Known

Application Number	10/687,288
Filing Date	October 15, 2003
First Named Inventor	Wang Yueh
Art Unit	1756
Examiner Name	Daborah Chacko Davis
Attorney Docket Number	42P17301

NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. ¹	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
		LAMMERS, DAVID, "Euro, Japan go to extremes for EUV," EE Times, 10/18/2002, 6 pages	
		ITO, H., "Chemical amplification resists: History and development within IBM," http://researchweb.watson.ibm.com/journal/rd/411/ito.txt , 1997 IBM, 12 pages	
		"Introduction to Electron Beam Lithography," http://dot.che.gatech.edu/henderson/introduction_to_electron_beam_lithography.htm , 13	
		Definition of 'PHOTORESIST' from Wikipedia, 2003, one page	
		MEDEIROS, D.R., ET AL., "Recent progress in electron-beam resists for advanced mask-making," IBM J. RES. & DEV. vol 45, no. 5, 09/2001, pps. 639-650	
		COBB, JONATHAN, ET AL., "Controlling line-edge roughness to within reasonable limits," Proceedings of SPIE Vol. 5039 (2003), pps. 376-383	
		LINTON, T., ET AL., "Determination of the Line Edge Roughness Specification for 34 nm Devices," TCAD Division, Intel Corporation, 2002 IEEE, pps. 303-306	
		STEWART, MICHAEL D., ET AL., "Diffusion Induced Line Edge Roughness," Advances in Resist Technology and Processing XX, Proceedings of SPIE Vol. 5039, 2003, pps. 115-122	

Examiner
SignatureDate
Considered

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Based on PTO/SB/08B (08-03) as modified by Blakely, Solokoff, Taylor & Zafman (w/r) 08/11/2003.
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